

PATENT ABSTRACTS OF JAPAN

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(71)Applicant : SUMITOMO CHEM CO LTD

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MURAKAMI SHINICHI**(54) PRODUCTION OF HIGH PURITY AQUEOUS HYDROGEN PEROXIDE SOLUTION****(57)Abstract:**

PURPOSE: To obtain a high purity aq. hydrogen peroxide soln. contg. diminished metals, chlorine ions and sulfuric acid radicals and used in a semiconductor producing process.

CONSTITUTION: When a crude aq. hydrogen peroxide soln. is purified to produce a high purity aq. hydrogen peroxide soln., the crude aq. hydrogen peroxide soln. is brought into contact with an anion exchange resin converted into a carbonate type with ammonium carbonate or an anion exchange resin converted into a bicarbonate type with ammonium bicarbonate.

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